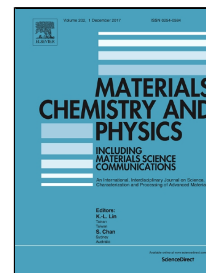


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Residual Stress Gradient of Cr and CrN thin films

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Highlights

- Residual stress at different penetration depths were calculated in thin films.
- The CrN thin film shows higher tensile residual stress at surface.
- The Cr thin film presents higher tensile stress at interface.
- The CrN phase in Cr/CrN/Cr/CrN thin film has lower tensile residual stress at surface.

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